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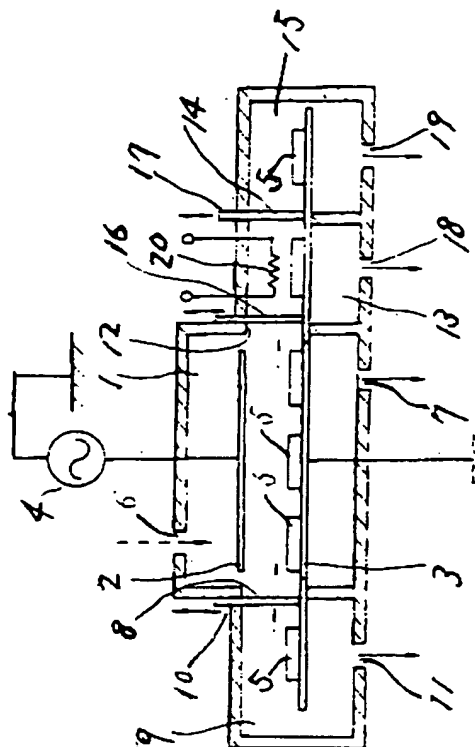
APPLICATION DATE : 06-09-82
APPLICATION NUMBER : 57153871

APPLICANT : HITACHI MICRO COMPUT ENG LTD;

INVENTOR : KOIKE ATSUYOSHI;

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TITLE : METHOD AND APPARATUS FOR
CHEMICAL REACTION OF GAS



ABSTRACT : PURPOSE: To remove a residual gaseous component in good efficiency, by a method wherein an object is processed by chemical reaction with reactive gas and the product is heated in an evacuated atmosphere reduced almost to zero absolute pressure.

CONSTITUTION: A residual gaseous component removing chamber 13 is connected to a reaction chamber 1 used in dry etching processing or the like so as to be capable of conveying a wafer 5 to be processed into said chamber 13 from the reaction chamber 1 as well as said chamber 13 is formed in a freely hermetically sealable manner and an electric heater 20 as a heating means and an exhaust port 18 for reducing pressure in the chamber 13 are further provided in the removing chamber 13. In the reaction chamber 1 of this apparatus, the object is processed by chemical reaction with reactive gas and the product is heated under almost zero absolute pressure in the chamber 13 to remove a residual gaseous component (e.g., fluorine, chlorine). The object to be processed can be prevented from corrosion caused by the residual gaseous component. In addition, because the residual gaseous component is heated in vacuum, the removal thereof can be performed within a short time.

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